

Monolithic CMOS Pixel Developments

Heinz Pernegger CERN/EP Department

10. Terascale Detector Workshop, DESY April 2017



High Luminosity - LHC





HL-LHC (High Luminosity LHC)

- Collisions to start mid-2026
- Maximum leveled instantaneous luminosity of 7.5 x 10³⁴ cm⁻² s⁻¹
 - Currently 1 x 10³⁴ cm⁻² s⁻¹
- 3000 fb⁻¹ Integrated luminosity to ATLAS over ten years
- 200 (mean number of) interactions per bunch crossing.
 - Original design for 25 interactions per bunch crossing



Challenges for the future

- Increased luminosity requires
 - Higher hit-rate capability
 - Higher segmentation
 - Higher radiation hardness
 - Lighter detectors
- Radiation hardness improvement compared to now
 - IBL approx. factor 5
 - Phase-2 approx. factor 10-30







- Secondary vertices reconstruction strongly depends on impact parameter resolution
 - d0 in r/phi (bending plane)
 - Z0 alone beam direction



- Impact parameter resolution is strongly effected by
 - Intrinsic point resolution and alignment at higher momentum
 - Multiple scattering in detector material (in particular for low pt tracks)
- Look for tracking solutions which combine small pixels with thin detectors
- They need to be radiation hard and include complex readout architectures to cope with high hit rates



The "World of Pixels" ...





Monolithic Pixels

- Charge generation volume integrated into the ASIC
- Used in ALICE ITS upgrade

Hybrid Pixels

- Sensor and ASIC are independent units
- Used in ATLAS and CMS pixel detectors



- Monolithic CMOS sensors sofar usually target "low-radiation environments"
- Hybrid Pixel detectors at pp colliders due to high radiation/hit rate





Monolithic

- Thin monolithic CMOS sensor (DMAPS) On-chip digital readout architecture
- Advantages for larger surfaces due to assembly simplification and costs
- Small pixel and thin detectors
 - e.g. 28x28 um & 0.3%/layer in Alice ITS
- Design limits for highest hit rates
- Radiation hardness limits

Hybrid

- Complex readout with zero-supression on in-pixel hit buffering
- Separately optimize sensor and FE-chip for very high radiation environment
- Copes with high hit-rates
- Thick detector modules (X0 1.7-2.7%)
- Expensive through fine-pitch bumpbonding



Monolithic Active Pixel Sensors

CMOS Sensors (MAPS) CMOS pixels with epitaxial layer as sensor



B. Dierickx, D. Meynants, G. Scheffer, SPIE 3410:68-76 (1998) R. Turchetta, ..., M. Winter et al, NIM A458 (2001) 677-689

STAR / RHIC MAPS



in operation since 2014

- CMOS process: use epitaxial layers as detection volume
- Limited to NMOS transistors
 - PMOS would result in competing nwell with charge collection electrode
- Sensors are fairly low power and allow e.g. air-cooling to minimize material
- Matrix typically read out with 3transistor rolling shutter architecture
- This makes them very attractive for applications of high spatial resolution requirements but lower radiation/hit rates, e.g. experiments at heavy ion – colliders like STAR HFT at RHIC



Monolithic Active Pixel Sensors

- Present state-of-art based on quadruple well allows full CMOS
- high resistivity (> 1kΩ cm) epi-layer (p-type, 20-40 µm thick) on psubstrate
- very small n-well diodes => small Cin
- moderate reverse bias => increase depletion region around Nwell collection diode

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3 Inner Barrel layers (IB)
4 Outer Barrel layers (OB)
Radial coverage: 21-400 mm ~ 10 m<sup>2</sup>
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0.3% X<sub>0</sub>/layer (IB)
0.8 % X<sub>0</sub>/layer (OB)
```

Radiation level (L0): 700 krad/10¹³ n_{eq} cm⁻²

See next presentation by W. Snoeys

10. Terascale Detector Workshop, DESY April 2017



TowerJazz 0.18um full CMOS process 6 metal layers

ALICE Inner Tracker System (ITS) Upgrade





Limitations

- For tracking MAPS appear to be the ideal detector
- BUT...
- Diffusion is the limiting factor:
- At high radiation (>10¹⁶ neq/cm²) ionization charge is trapped in nondepleted part – No more signal
- Diffusion make signal collection slower than typical requirements for pp-colliders



 Readout architectures are low power but not designed for high hit-rates like pp at LHC



Monolithic CMOS Pixels for pp-collisions at HL-LHC?



CMOS Pixel Collaboration

Collaboration of ~25 ATLAS ITK institutions





Outer layers

- Given by ATLAS radiation level, hit rates and bunch structure for ITK Pixel detector
 - 25ns BC
 - L1 trigger rate 4MHz





Hitrates per module in different layers

- µ=200
- Pixel 50x50x (150µm depletion)
- Module size 33.8mm (phi) x
 40.3mm (z) (or 16.9x40.3 for L0)
- Look at average number of hits per module or per column per BC
- <hits/mod> Layer 0 = 464 and Layer 1 = 289
- <hits/mod> Layer 2 = 59, Layer 3=40 and Layer 4 = 29
- Tails up to 4x average

	Average channel Hit rate /mm2 per BC at μ =200
Layer 0	0.68
Layer 1	0.21
Layer 2	0.043
Layer 3	0.029
Layer 4	0.021



Roland Jansky (Innsbruck)

H. Pernegger

10. Terascale Detector Workshop, DESY April 2017



Radiation hardness: develop CMOS sensors that...

- Collect charge by drift not diffusion!
- Analog designs : Demonstrated radiation hardness to ATLAS levels (10¹⁴ to 10¹⁵ to 10¹⁶ n_{eq}/cm²) and fast (25ns BC)
- Digital integration of complex readout architectures with ATLAS specs in monolithic sensors
 - Implementing full readout architecture into limited space of pixel (50x50um)
 - Avoid cross-talk from digital activity into sensor part/analog section
- System Integration of CMOS sensors to modules "Drop-in" Quad modules using CMOS sensors
 - Demonstrate assembly and QA on module & stave level
 - Compatible with mechanical, thermal and electrical ITK Pixel system design



Depleted CMOS sensors

- To overcome the limitations of "classic"
 MAPS we need depletion
- Depletion = fast charge collection (25ns BC)
- Depletion = less charge trapping after irradiation (>10¹⁵ n_{eq}/cm²)
- Promise for radiation hard and fast CMOS sensors



- Create a large depleted volume under n-well -> this serves as volume for particle detection
- Electronics is include in sensor pixel

 -> "Smart Pixel" allows processing of
 information on sensor
- Depleted Monolythic Active Pixel Sensor (DMAPS)



- We need to optimize the charge collection for
 - Fast charge collection to avoid trapping after irradiation
 - Large depletion region for high(er) signals



- Combine HR & HV to get large depleted volume with fast charge collection by drift
- Aim at depletion region of 40 to 80 μm (~4000 e-)

$$d \propto \sqrt{\rho V}$$

- High Q/C -> high voltage swing on input amplifier (detection of signals from thin depletion layers if C small)
- 25ns in-time efficient
- Reasonable short drift paths to avoid large trapping after irradiation



Enabling technologies

• The design of Depleted Monolithic Active Pixel Sensors relies on several process technologies:

- "High" Voltage
add-onsSpecial processing add-ons (from automotive and power management
applications) increase the voltage handling capability and create a
depletion layer in a well's pn-junction of o(10-15 μm).
- "High" Resistive
Wafers8" hi/mid resistivity silicon wafers accepted/qualified by the foundry.
Create depletion layer due the high resistivity.

Technology features
(130-180 nm)Radiation hard processes with multiple nested wells.
Foundry must accept some process/DRC changes in
order to optimize the design for HEP.



from: www.xfab.com

Backside Processing

Wafer thinning from backside and backside implant to fabricate a **backside contact** after CMOS processing.



Analog design & Fill factor

Large fill factor

- Uniform charge collection
- Large capacitance (~50-200 fF) on CSA
- More power necessary to achieve fast signals with reasonable amplitude



Small fill factor

- Higher gain and faster response due to smaller capacitance (2-5fF) and higher Q/C
- Potentially lower power consumption
- Signal collection under DPW after irradiation more difficult on edges



Schematic cross-section of CMOS pixel sensor (ALICE ITS Upgrade TDR)



Large electrodes pixel sensors in LFoundry



LFA150:

- L-Foundry 150 nm process (deep N-well/P-well)
- Up to 7 metal layers •
- Resistivity of wafer: >2000 Ω·cm •
- Small implant customization •
- Backside processing

CCPD LF prototype:

- Pixel size: 33um x 125 μ m (6 pix =2 pix of FEI4)
- Chip size: 5 mm x 5 mm (24 x 114 pix)
- Bondable to FEI4 (+pixel encoding) ٠
- 300um and 100um version
- Bonn + CCPM +KIT



P. Rymaszewski et al., JINST 11 (2016) 02 C02045 T. Hirono et al., doi:10.1016/j.nima.2016.01.088



CCPD LF

- Subm. in Sep. 2014
- $33 \times 125 \ \mu m^2$ pixels
- Fast R/O coupled to **FE-I4**
- Standalone R/O for test
- (Almost) Fully characterized



- Subm. in Mar. 2016
- **CPIX** demonstrator in LF
- $50 \times 250 \ \mu m^2$ pixels •
 - Fast R/O coupled to FE-14
- Standalone R/O for test ٠

First meas. available

LF-Monopix01 (monolithic)

- Subm. in Aug. 2016
- "Demonstrator size" ٠
- $50 \times 250 \ \mu m^2$ pixels •
- Fast standalone R/O •
- Standalone R/O like LF-CPIX



de l'Univers

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universitätbo



3.2GeV electrons beam tests

PW

PSUB

Large Fill Factor Cell

Version A

Pixel: CSA ELT

Source: 55Fe

Bias: 110V (4nA)



Version B Bias: 20V (39nA) Pixel: HV connection Diode, CSA ELT, PSUB everywhere Source: ⁵⁵Fe







Edge-TCT measurements on LFounrdy CPIX



I. Mandic, B. Hiti (Ljubljana)

Neutron irradiated CPIX sensors up to 2x10¹⁵ neq/cm²



parameters

charge (arb. Preliminary! 300 FWHM (µm) = 5e13 neg cm⁻² 120 = 1e14 neg cm⁻² 250 = 5e14 neq cm⁻² 100 = 1e15 neq cm⁻² 200 Φ = 2e15 neq cm⁻² 80 V_{bias} = 250 V 150 60 100 40 50 20 -50100 150 200 250 300 350 400 450 0 50 y (μm)

Width of charge collection region at 50% max





Chip overview

- Large input from LF-CPIX: pixel, floor plan...
- 9 flavors for comparative studies =>
- each 4 col.
 - Pixel with R/O logic (FE-I3 like pixel)
 - □ NMOS/CMOS pre-amp.
 - Different power domains for discri.
 - □ CS /CMOS token transmission
 - · Binary pixel with R/O logic at column end
 - □ faster pre-amp. & discriminator

PADs + Serializer +LVDS driver					
Sense Amplifiers + Gray Counters + EoC R/O					
Logic Decoupling capacitors	R/O logic				
Pixel with R/O logic	Binary pixe				
129 X 28	129 X 8				
(7 designs)	(2 designs)				
Chip Bias, Configuration & Monitoring					
PADs Procession and an an					

Tomasz Hemperek / Uni-Bonn

- Many design efforts to meet the challenges in terms of noise and timing
 - □ full-custom in-pixel digital circuit & low noise digital block



LF-Monopix01: key design ingredients





- Capacitively Coupled Pixel Detectors (H18 AMS process)
 - Capacitive-Coupling of CMOS sensor to ATLAS FEI4 (sensor pixel size 33x 125um2)
 - Blocks for monolithic design implemented and studied (DAC, Amplifier, Discriminators, Configuration)

y-position [µm]

1000

-500

- Efficiency of > 99.5%
- Signal collected in 3BC

H18 CCPDv5

- First prototype in aH18 process (Hi-Resistivity wafer processing)
- Many beam tests carried out to test operation, tuning, achievable threshold and efficiency
 - 600-650e Threshold



Threshold before and after equalization

T. Weston/ Uni Bern @ TREDI 2017



AMS H35DEMO sensor



Eva Vilella / Uni Liverpool

- ams 0.35 μm HV-CMOS (H35)
- submission through an engineering run
 - submission in October 2015
 - wafer production finished in December 2015
- different substrate resistivities to improve SNR
 - 20 Ω ·cm (standard), 80 Ω ·cm, 200 Ω ·cm, 1k Ω ·cm

Areas (from top to bottom):

- standalone nMOS matrix
 - digital pixels with in-pixel nMOS comparator
 - standalone readout
- analog matrix (2 identical arrays)
 - different flavours
- standalone CMOS matrix
 - analog pixels with off-pixel CMOS comparator
 - standalone readout
- All pixels are 50 μm x 250 μm for compatibility with FEI4



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AMS H35 Demonstrator

T. Weston/ Uni Bern @ TREDI 2017



Cluster Size = 1

- Events where 1 pixel fired
- Most collected in centre

• Events where 2 pixels fired April 2017

• Most collected at edges

Cluster Size = 2

28

pixel flavours



Changes of Neff in CMOS sensors





Monolithic submission in AMS H18

- Combined submission between Mu3e and Atlas
- See presentation about MuPix by F. Meier-
- Project MuPix8/ ATLASPix (2016)
 Rad-hard MuPix
- Technology AMS aH18 (180nm)
- Substrates: 20, 50-100, 100-400, 600-1100 Ωcm
- 4-well HVCMOS process
- Main features (Atlas part):
- Pixel pitch 56x56um
- Asynchronous readout to periphery
- Buffering of hits in pixel (-groups)



MuPix, ATLASPIX

I. Peric / KIT@ TREDI 2017



- On sensors described so-fare, the analog & digitial circuit is placed inside collection well
- Input capacitance is dominated by additional capacitance between nwell and p-well

hybrid planar pixels (e.g. ATLAS IBL): **Cin = 109 fF** (Havranek et al, NIMA 714 (2013) 83-89 CMOS pixel extrapolation: **Cin ≈ 200 fF**



H. Krüger / Bonn

- Response time: $\propto \frac{1}{g_m} \frac{\mathbf{C_d}}{C_f}$
- Noise:

$$ENC_{thermal}^2 \propto \frac{4}{3} \frac{kT C_d^2}{g_m \tau}$$

Total input capacitance drives peaking time and ENC Counteract by increasing transconductance – but this increases power consumption significantly

- Additionally digital signals are contained in collection well hence risk
 of severe cross-talk of digital signals to collection well
 - Can be minimzed by special source follower (P. Rymaszewski / Bonn)



TowerJazz 180nm Investigator



Designed as part of the ALPIDE development for the ALICE ITS upgrade

Emphasis on small fill factor and small capacitance enables low analog power designs (and material reduction in consequence)

C. Gao et al., NIM A (2016) 831 http://www.sciencedirect.com/science/article/pii/ S0168900216300985

Produced in TowerJazz 180nm on 25-30um thick epi layer

Design: C. Gao, P. Yang, C. Marin Tobon, J. Rousset, T. Kugathasan and W. Snoeys



Smaller capacitance => better Q/C



- Reducing the detector capacitance increases the signal amplitude at the input (Q/C) and therefore yields better S/N and faster signal
- Can be used to reduce power consumption (and therefore services and cooling material).
- Simulated a very similar front end increasing power consumption ~ To match ATLAS ITK requirements we use up to 500nA nA (= 70 mW/cm² for 36 µm pitch) aiming at timewalk of less than 15ns



Small collection electrodes



Schematic cross-section of CMOS pixel sensor (ALICE ITS Upgrade TDR)

Modified Process

- Add planar n-type layer
- Significantly improves depletion under p-well with deep junction
- Does not require significant circuit or layout changes

Small collection electrodes

- Higher gain and faster response due to smaller capacitance (~5fF) and higher Q/C
- Potentially lower power consumption
- Signal collection under DPW after irradiation more difficult on edges





- Normally small electrodes produce weak fields under p-well and charge gets lost after irradiation
- This usually means that efficiency drops significantly towards pixel edges
- Modified process allows to improve the efficiency after irradiation on pixel edges while keeping small capacitance which makes this in particular interesting for fast charge collection after irradiation





TJ Neutron irradiation to 10¹⁴ and 10¹⁵ n/cm²

- Investigator irradiated by IJS Ljubljana in several steps up to 10¹⁵
- Measurements up to 10¹⁶ ongoing
- This detector has received NIEL 10¹⁵ n/cm2 and 1Mrad TID





- Plot calibrated signal versus charge collection time on 50x50um pixel pitch
- Very little change is signal response after 10¹⁵ n/cm²
- Standard process after 10¹⁵ n/cm² does not give measureable signals anymore





 First preliminary e-TCT measurements on 20x20 and 50x50um pitch shows depletion of epi even after 10¹⁵ n/cm2 at -6V





TJ Investigator efficiency

- Unirradiated sensor efficiency 98.5% ± 0.5% (stat) ± 0.5% (syst)
 - slightly reduced efficiency due to high threshold in testbeam (~640eneeded because of common mode noise during measurements)





 Irradiated sensor of 25x25 and 30x30um pitch show uniform efficiency across pixel





- Measurements show that a low capacitance and radiation hard design towards Atlas Outer Layers is possible using a small-fill factor collection well in the modified TowerJazz 180nm process
- We have moved now towards a dedicated full-size monolithic sensor chip design which matches ATLAS specs
 - Analog front-end with CSA+discriminator tuned optimized for 25ns in-time efficiency and low threshold operation
 - 2x2cm chip size with <50x50um pixels</p>
 - Monolithic design includes readout architecture which copes with ATLAS outer layer hit rate requirement



Front-end for Atlas

- Prepared two large chips based on Atlasoptimized Front-end design for small fill factor
- MALTA chip and MonoPix chip



Each pixel = CSA + discriminator + Flip/flop

- 36.4 x 36.4 um pixel pitch
- Including analog test pulse
- Including pixel mask
- Diode & PMOS reset implemented
- Discriminator Leading edge output injected to double column pixel logic
- Analog measurement through ToT (LE/TE) or LE time difference to ref signal on periphery
- Bias current 200nA to 500nA can be used to adjust TW range



Full-size chip Matrix: Two Architectures

• TJ MALTA

Full matrix = 512x512 pixels Design/CERN

- Active area 18 x 18 mm²
- Hit memory in active matrix
- All hits are Asynchronously transmitted over high-speed bus to EoC logic
- No clock distribution over active matrix to minimize power and digital-analog cross-talk

TJ MonoPix

512x256 pixels Design/Bonn

- Active area 18 x 10 mm²
- Hit memory in active matrix (2 flip-flop per pixel)
- Synchronous column drain architecture
- Hit address asserted to bus with 40MHz token
- 6 bit ToT coding at end of column



EoC Chip bus – asynchonous hit address transmission

Design Team: W. Snoeys, T. Kugathansan, C. Marin Tobon, I. Berdalovic, R. Cardella, N. Egidos (CERN) J. Rousset, B. Blochet (MIND), K. Moustakas, T. Wang (Bonn)



Current CMOS RD in ATLAS (2017-18)

TowerJazz

- Subm. in May. 2017
- Two large scale demonstrators MALTA and Monopix:
 - 20x20mm and 20x10mm
 - Focus on small FF pixel
 - Asynchronous matrix readout (no clock distribution over the matrix)
 - Column Drain Read-Out (based on Monopix)



<u>AMS H180</u>

- Mu3E + ATLAS (monolithic)
- Subm. In Jan. 2017
- Additional production step

 isolated PMOS
- 80 and 200 Ohm.cm wafers
- Reticle Size about 21mm x 23mm



LFoundry

Monopix01, LF2 and Coolpix1

- Received Apr. 2017
- "Demonstrator size"
- 50 x 250 µm² pixels
- Fast standalone R/O



CERN, 21 November 2016



The Matrix (Pixel Level)

•	All of our present CMOS sensor designs	CMOS chip	Fill Factor	Pitch [um x um]
	discriminator + Hit Memory	AMS 180	Large	56x56
	 Including analog test pulse 	TJ Malta	Small	36x36
	 Including pixel mask 	TJ Monopix	Small	36x40
	 Diode or PMOS reset 	LF Monopix and	Large	50x250
	 Discriminator with edge output injected to 	Coolpix		
	double column pixel logic	LF2	Large	50x50
	 Hit memory in active matrix 			
	 Control of bias current (individual or on chip level) 	CMOS RO	Architecture	
• Fu	Full matrix needs = <512x512 pixels	AMS 180	Asynchronous	
	- Cover active area $\sim 18 \times 20 \text{ mm}^2$ (assuming			
	FEI4-like coverage – tbc by ITK Module)	TJ Malta	Asynchronous	
	 Coarse analog measurement (LE/TE time difference and bunch crossing ref signal on 	TJ Monopix	Synchronous	
	periphery)	LF Monopix and	Synchronous	
	 All pixel addresses with hits are 	Соогріх		
	(a)synchronously transmitted over high-	LF2	Synchrono	ous



 Follow two main concepts for pixel matrix readout with ATLAS ITK specs for outer layers

1. Column drain architecture

- Token distribution through column, synchronous readout of pixel buffers
- Include hit buffering (leading edge, trailing edge) in pixel
- Submission now back: LF MonoPix1 , LF2 and Coolpix 1

2. Asynchronous hit direct to periphery

- Comparator output directly to periphery
- Buffering and time-stamp at periphery
- Two submissions in preparation: AMS180/LF150 and TJ180
- Main performance criteria that are addressed with these prototyping chips towards ATLAS specifications
 - Hit rate capability
 - Matrix "noise and threshold" performance (cross talk between sensor analog and digital part)
 - In-time efficiency and time-walk measurements
 - Minimize power consumption in active matrix part
- Provide CMOS sensors for ITK Module Prototypes and System Integration tests



DC Data transmission – hit loss

- Multiple hits per cluster taken care of by architecture
- Is there a limitation through th number of clusters in DC?
 - Average cluster rate 0.003 (L4) to 0.1 (L0) clusters/mm2 per BC
 - Note: results will depend on pixel pitch and buffer logic or pixel sub-grouping
- Check probability to have >1 cluster in DC logic (number e.g. of MALTA)
 - Layer peak cluster rates ~ x5 average rate
 - To accommodate peak rate in outer barrels assume e.g. 2Mclusters/mm2s) anywhere in the half-double-column
 - P(x>1, λ=0.66mm2*0.05 cluster/ BC*mm2) = 0.05%



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End of Column - Periphery

- End of Column
 - Merges hit pixel address signals on wide chip data bus
 - Adds time stamping to identify bunch crossing
- Chip data bus
 - Contains hit/time information of all hits in the chip
 - Data output can be switched to output stage either as parallal bus or serializer
 - Contains output driver
 - Additional Config input & SR
 - Contains biasing network & DACs



Chip bus – asynchonous hit address transmission



- Hybrid Baseline for Outer layers require 4 chips per module onto single data output
- Baseline requires a Multi-Chip Controller (now called Data Concentrator) like present pixel on outermost layer
- ITK pixel requirement to this MCC
 - Trigger rate 4MHz with latency up to 12.5 or 20 us
 - IO compatible to RD53 (ATLAS-1) to use same readout on inner and outer layers
- Chip-chain to "Multi-Chip Controller" (MCC)
 - Chip0 Chip1, Chip2, Chip3 data sent to MCC





- Module flex
 - 4 CMOS sensor chips (each ~19x20mm²)
 - Carries MCC
 - Power routing to CMOS chips
 - Module IO connector identical to Hybrid Quad module









- There is a large momentum in R&D for CMOS active monolithic pixels sensors as an attractive direction for LHC experiments, even pp-experiments
- CMOS sensors are pursued as promising option for the pixel (outer) layers of the HL-LHC Atlas ITK Pixel Detector
- Through combination of high-resistivity wafers and/or HV process options combined with dedicated pixel cell designs, we have achieved radiation hardness of CMOS sensors beyond 10¹⁵ neq/cm² with several different designs and foundries
- We currently develop a large set of readout architectures to cope with hit rates of (outer) pixel layers in Depleted Monolithic Active Pixel Sensors
- This development of fast thin radiation hard CMOS sensors may provide very interesting sensors for tracking detector at future colliders



- ... to the organizers for the possibility to participate this nice workshop!
- ... to my colleagues contributing to this presentation
 - N. Wermes
 - W. Snoeys
 - P. Riedler
 - T. Hemperek
 - H. Krüger

- E. Vilella
- I. Peric
- T. Weston
- M. Benoit
- B. Hiti



Backup



- Rise time versus amplitude shows significant fraction of "diffusion" signals
 - Signal collection speed increases with substrate voltage for shared hits





- No change in rise time with or without sharing
- Charge collected purely by drift



H. Pernegger CERN EP - TREDI - Trento Feb 2017



 Unirradiated 50x50um and 10¹⁵ n/cm² irradiated 25x25 and 30x30um pixel sensors



- Spacing between DNW and DPW also influences charge sharing
- 25x25 and 30x30um have spacing 3um
- 50x50 has spacing 18.5um



Testbeam SPS

- Beamtests at SPS with 180GeV pions on unirradiated and irradiated after 10¹⁵ n/cm² sensor
- Unirradiated 50x50um pitch sensor with large spacing (18.5um)





Signal versus position on four 50x50um pixels



- Upgrade of Accelerator System to achieve high beam intensity
- Upgrade of Experiments:
 - Tracker will be replaced for better precision and high rates & radiation
 - New Trigger systems are essential to select rare events & new physics
 - New DAQ system & Reconstruction software to cope with

H. Perne Rormous data volume ale Detector Workshop, DESY April 2017



ATLAS IBL in Run 2

